

In the claims:

Please substitute the following full listing of claims for the claims as originally filed or most recently amended.

1. (Currently amended) A lithography system, comprising:

a reticle chamber containing a reticle stage component extending between portions of an optics system,

said reticle chamber having a reticle chamber opening that provides direct access to ~~a~~said reticle stage within ~~the~~said reticle chamber so that ~~the~~said reticle stage can be accessed or removed through ~~the~~said reticle chamber opening and from between said portions of said optics system without disassembly of components of said optics system.

Claim 2 has been cancelled.

3. (Currently amended) The lithography system of claim 1, wherein ~~the~~said reticle stage component includes a reticle stage and a reticle table, wherein said reticle stage component is removable from ~~the~~said reticle chamber in a first direction which is in a plane substantially horizontal to ~~a~~said reticle table mounted to ~~the~~said reticle stage.

4. (Currently amended) The lithography system of claim ~~1~~21, wherein ~~a~~said reticle chamber maintenance panel is pivotably mounted to ~~the~~said reticle chamber.

5. (Currently amended) The lithography system of claim 1, wherein ~~the~~said reticle chamber opening is at an angle substantially equal to or between 0° and 45° with relation to ~~the~~said reticle chamber.

6. (Currently amended) The lithography system of claim 1, wherein ~~the~~said reticle chamber opening is at an angle at or greater than 45° with relation to ~~the~~said reticle chamber.

7. (Currently amended) The lithography system of claim 1, ~~further comprising wherein said optics system~~  
comprises:

a projection optic system; and  
an illuminator optic system; ~~and~~

wherein said ~~a~~ reticle table mounted to ~~the~~said reticle stage ~~and is~~ positionable between ~~the~~said projection optic system and ~~the~~said illuminator optic system.

8. (Currently amended) The lithography system of claim ~~1-7~~, wherein ~~a~~said reticle table and ~~the~~said reticle stage are removable through ~~the~~said reticle chamber opening in a plane which is substantially perpendicular to a source illuminating from ~~the~~said illuminator optic system.

9. (Currently amended) The lithography system of claim ~~1-7~~, further comprising a body structure which is mounted to a lower portion of the reticle chamber, ~~a~~said projection optic system and ~~an~~said illuminator optic system being mounted to ~~the~~said body structure.

10. (Currently amended) The lithography system of claim ~~1-21~~, wherein ~~the~~said reticle chamber maintenance panel is semi-cylindrically shaped.

Claim 11 has been cancelled.

12. (Currently amended) The lithography system of claim 1, wherein ~~the~~said reticle chamber opening provides access to substantially a center of gravity of

~~the-said~~ reticle stage.

13. (Currently amended) A lithography system, comprising:

a reticle chamber having a reticle chamber angled opening,

a reticle chamber maintenance panel which is removably mounted to the reticle chamber over the-said reticle chamber angled opening;

an optical system for illuminating and projecting a source;

a reticle stage having a reticle table, ~~the-said~~ reticle table positioned between components of ~~the-said~~ optical system and housed with ~~the-said~~ reticle stage within ~~the-said~~ reticle chamber,

wherein ~~the-said~~ reticle chamber angled opening provides access to ~~the-said~~ reticle stage.

14. (Currently amended) The lithography system of claim 13, wherein ~~the-said~~ reticle chamber angled opening provides access to ~~the-said~~ reticle stage at substantially a center of gravity.

15. (Currently amended) The lithography system of claim 14, wherein ~~the-said~~ reticle stage is removable from ~~the-said~~ reticle chamber via ~~the-said~~ reticle chamber angled opening.

16. (Currently amended) The lithography system of claim 14, wherein ~~the-said~~ reticle stage is removable from ~~the-said~~ reticle chamber via ~~the-said~~ reticle chamber angled opening in a first direction which is in a plane substantially ~~horizontal~~ parallel to the reticle table.

17. (Currently amended) The lithography system of claim ~~13-18~~, wherein ~~the-said~~ reticle chamber

maintenance panel is pivotably mounted to the reticle chamber.

18. (Currently amended) The lithography system of claim ~~13~~ 16, wherein ~~the said~~ reticle ~~angled~~ chamber angled opening is at an angle of approximately 45° with relation to ~~the said~~ reticle chamber such that ~~the said~~ reticle chamber maintenance panel is removed, ~~the said~~ reticle stage partially extends from ~~the said~~ reticle chamber.

19. (Currently amended) The lithography system of claim ~~13~~ 16, further comprising a body structure which is mounted to a lower portion of ~~the said~~ reticle chamber, ~~the said~~ projection optic and ~~the said~~ illuminator optic being mounted to ~~the said~~ body structure during the removal of ~~the said~~ reticle table and ~~the said~~ reticle stage.

20. (Currently amended) The lithography system of claim ~~13~~ 18, wherein ~~the said~~ reticle chamber maintenance panel is semi-cylindrically shaped.

21. (New) The lithography system of claim 1, further comprising a reticle chamber maintenance panel, wherein said reticle chamber maintenance panel is removably mounted to said reticle chamber over said reticle chamber angled opening.